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(54) Title: A METHOD OF GENERATING A PATTERN ON A SUBSTRATE

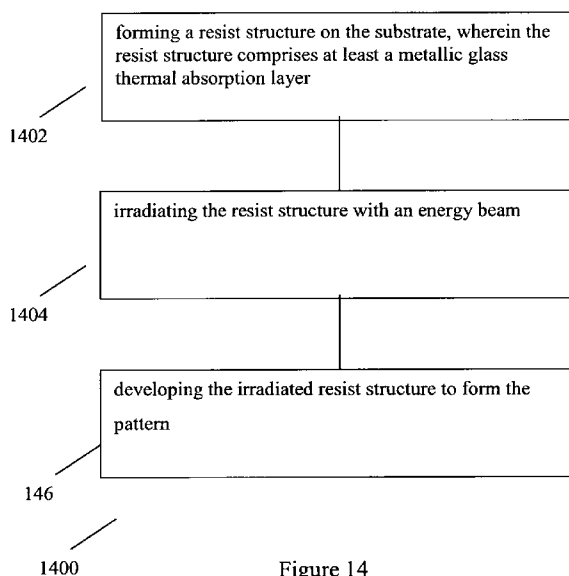


Figure 14

(57) Abstract: A method of generating a desired pattern on a substrate, and a pattern on a substrate formed using the method. The method comprises forming a resist structure on the substrate, wherein the resist structure comprises at least a metallic glass thermal absorption layer, irradiating the resist structure with an energy beam, and developing the irradiated resist structure to form the desired pattern.



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